IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PRIORITY Application Serial No	10/323,525
PRIORITY Filing Date	
Inventor	
Assignee	Micron Technology, Inc.
PRIORITY Group Art Unit	2824
PRIORITY Examiner	Christian D. Wilson
Attorney's Docket No	
Title: Microelectronic Device Fabricating Methods,	and Methods of Forming
a Pair of Field Effect Transistor Gate Lines	of Different Base Widths
From a Common Deposited Conductive Layer	•

PRELIMINARY AMENDMENT

To:

Mail Stop Patent Application Commissioner for Patents

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Please enter the following amendments prior to examining the aboveidentified application.

AMENDMENTS